

PATTERN INSPECTION METHOD AND APPARATUS

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ABSTRACT OF THE DISCLOSURE

10 A pattern inspection method and a pattern inspection
apparatus, which has an improved precision in detecting
and correcting the positional deviation of images for a
die comparison, have been disclosed. The quantity of
correction of positional deviation of the images for the
die comparison is determined based on the positional
information of the images at multiple separate places in
15 a die (pattern). For example, the multiple separate
places include the vicinities of both ends in the pattern
arrangement to be scanned in the die, and the part where
the inspection is not completed yet. When the positional
information of the part where the inspection is not
20 completed yet is used, the correction of the positional
relation of the images to be compared and the comparison
of the images are started immediately after the capture
of the images of two patterns is completed.